

Supporting Information

Green Light Sensitive Diketopyrrolopyrrole Derivatives used in Versatile Photoinitiating Systems for Photopolymerizations

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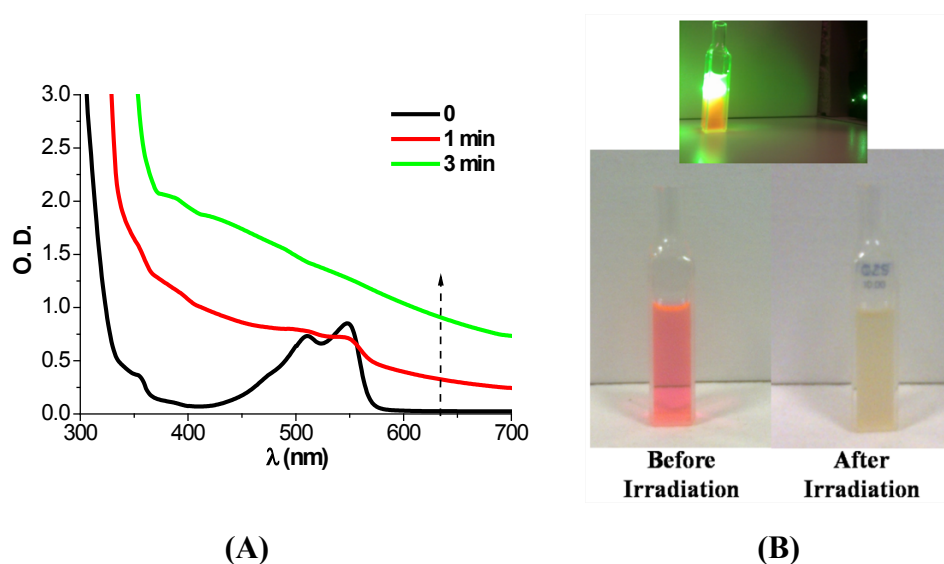


Figure S1. (A) Steady state photolysis of **DPPDT/MDEA/R'-Cl** in tetrahydrofuran upon the laser diode at 532 nm exposure under air; $[MDEA] = [R'-Cl] = 1.0 \times 10^{-2}$ M. UV-vis spectra recorded at different irradiation times; (B) **DPPDT/MDEA/R'-Cl** in tetrahydrofuran before, during and after the laser diode at 532 nm irradiation.